

BGD Group – 2011 TLC Developing System

The following solvent systems are roughly ordered from least polar to most polar. For multi-solvent systems, the polarity will depend on the solvent ratio

*Good (more usual) systems that are most often used that run quickly and vac-off cleanly/well - efficient

Pentane
Hexane or Petrol
Petrol/Ether
THF/Petrol
THF/Ether
THF/EtOAc
THF/MeOH
*Petrol/EtOAc
Acetone/Toluene

a change in solvent type can pull apart two spots that might have the same R_f in a different solvent system with the same polarity – solvent:solute interactions are molecular too so change the solvent structure if you need to

Acetone/Petrol
EtOAc
Toluene/EtOAc
Et₃N/EtOAc

(good for aromatic compounds)
(up to 5% Et₃N, use for basic compounds or those that are acid sensitive and so decompose on silica - Et₃N may be hard to vac-off so use 0.1% is you can)

DCM
Petrol/DCM
Acetone/DCM
Et₂O/DCM
*EtOAc/(Hexane/Petrol)
EtOAc/DCM
EtOH/DCM
EtOH/CHCl₃
Ether/MeOH
CHCl₃/Acetone

(good for halogenated protected sugars, e.g 1:50)

*MeOH/EtOAc

(good for free hydroxyl group)
(good for separation of protected anomeric mixture, e.g. 97:3)
(good for protected sugars, up to 20% MeOH, + 1-2% AcOH in presence of acid impurity)
Remember >20% MeOH in EtOAc will start to dissolve some silicas giving you a fine white powder/crystals on vac-down and a yield of >100%!
(use for acidic compounds, 1-5% AcOH)
(up to 20% MeOH)

AcOH/EtOAc
MeOH/DCM
*MeOH/CHCl₃
*i*PrOH/EtOAc
*i*PrOH/CHCl₃
BuOH/AcOH/H₂O
NH₄OH/MeOH/DCM

BuOH can be quite unique for some compounds
(for basic compounds, 1-10% NH₄OH, 25% aq.)

*CHCl₃/MeOH/Acetone/H₂O
*CHCl₃/MeOH/AcOH/H₂O

CMAW or "Seymour"

H₂O/THF/Ether
H₂O/MeCN
H₂O/*i*PrOH/Ether
H₂O/*i*PrOH/EtOAc + 100mM NaCl
H₂O/*i*PrOH/EtOAc
EtOH/NH₄(aq.)/H₂O
H₂O/*i*PrOH/EtOAc + 1% NH₄ (aq.)
H₂O/CHCl₃/MeOH/AcOH
H₂O/AcOH/MeOH/EtOAc
NH₄OH/MeOH/*i*PrOH

(for very polar compounds; up to 1:2:2)

(for very polar, basic compounds like deprotected amino acids; up to 10% NH₄OH and 20% MeOH)